

Form PTO 1449 (Modified)		U. S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  LIST OF REFERENCES CITED BY APPLICANT		ATTY DOCKET NO. 293482US0PCT	SERIAL NO. 10/588,080	
				APPLICANT Naoyoshi HATAKEYAMA, et al.		
				FILING DATE January 10, 2007	GROUP 1762	1621
U. S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
	AA					
	AE					
	AC					
	AD					
	AF					
	AF					
	AC					
	AH					
	AI					
	AJ					
	AK					
	AJ					
	AM					
	AN					
FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO	
/VV/	AO	WO 03/104182 A1	12/18/2003	WIPO		
/VV/	AP	EP 0 999 474 A1	5/10/2000	Europe		
/VV/	AQ	EP 1 577 285 A1	9/21/2005	Europe		
/VV/	AK	EP 1 803 708 A1	7/4/2007	Europe		
	AS					
	AT					
	AU					
	AV					
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)						
/VV/	AW	K. E. GONSALVES, et al., "High performance resist for EUV lithography", DATABASE CA [ONLINE], CHEMICAL ABSTRACTS SERVICE, XP-002461455, accession no. 2004: 1001937, Microelectronic engineering, 2005, 1 Page				
	AX					
	AY					
	AZ					
					<input type="checkbox"/> Additional References sheet(s) attached	
Examiner		/Yevgeny Valenrod/			Date Considered 03/23/2009	
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.						